Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number	Application Number
12-1233	Herewith
Applicant	
Lammert	
Filing Date	**Group Art Unit**
Herewith	N/A

jc715 U.S. PTO 10/016693 10/30/01

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
	5 3 5 2 9 1 1	10/04/1994	Grossman	257	198	10/28/1991
	5 4 8 6 4 8 3	01/23/1996	Lammert	438	6666	09/27/1994
	5 8 0 4 4 8 7	09/08/1998	Lammert	438	319	02/10/1996
	5 9 9 4 1 9 4	11/30/1999	Lammert	438	319	05/09/1998

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	Translation Yes	Translation No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Schuppert, et al., "Anisotropic Plasma Etching of Polymers Using a Cryo-Cooled Resist Mask, J. Vac. Sci. Technol. A 18(2), March/April 2000, pages 385-387
	Zhao, et al., "Reactive Ion Etching of Silicon Containing Polynorborenes", School of Chemical Engineering, Georgia Institute of Technology, pages 1-30.

EXAMINER Julio J. Maldonado DATE CONSIDERED 01/11/2002

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.